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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

plicants: Choi et al.

Patent Application

erial No: 09/698,317

Group Art Unit: 1763

Oct. 27, 2000 Filed:

Examiner: Roberts P. Culbert CL ONTROL ONTROL ONDER 12003 ED For: HIGH PRECISION ORIENTATION ALIGNMENT AND GAP CONTROL

STAGES FOR IMPRINT LITHOGRAPHY PROCESSES

## **AMENDMENT**

Commissioner for Patents Alexandria, VA 22313

Sir:

In response to the Restriction Requirement mailed May 16, 2003, please amend the application as follows:

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## IN THE DRAWINGS:

Applicant proposes to Amend Figs. 4, 6, and 11 of the patent application to harmonize with the description of the invention in the written Specification. To that end, a separate letter to the Chief Draftsperson is attached requesting that the Drawings be corrected.

Fig. 4 has been amended to include elements 110 and 114 as indicated on the accompanying drawings.

Fig. 6 has been amended to include elements 210 and to show frame 130 and re-label the same as element 206 as indicated on the accompanying drawings.

Fig. 11B has been amended to show wall shape 462 and re-label the same as element 464 and to show smooth curved cross section 462 and re-label the same as element 466 as indicated on the accompanying drawings.

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